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(71) Applicant (*for all designated States except US*): **NIKON CORPORATION [JP/JP]; 2-3 Marunouchi, 3-chome, Chiyoda-ku, Tokyo, Tokyo 100-8331 (JP).**

(72) Inventors; and

(75) Inventors/Applicants (*for US only*): **ALTON, Phillips, H. [US/US]; 480 E. Okeefe Street, #304, East Palo Alto, CA 94303 (US). SOGARD, Michael, R. [US/US]; 516 Placitas Avenue, Menlo Park, CA 94025 (US). WATSON,**

Douglas, C. [US/US]; 1353 Cameo Drive, Campbell, CA 95008 (US). TANAKA, Keiichi [JP/JP]; 7-7-40-1416, Kamiochiai, Chuo-ku, Saitama-ken, Saitama-shi, Saitama 338-0001 (JP).

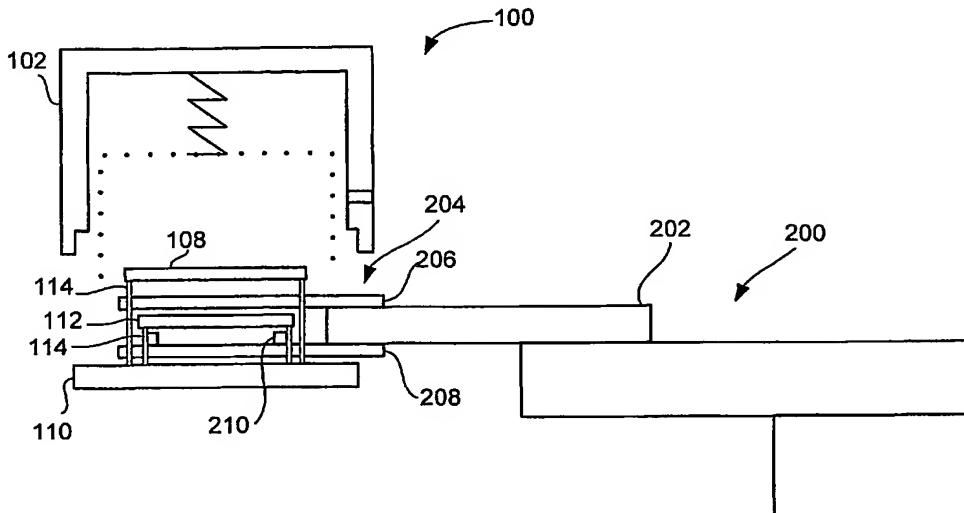
(74) Agent: **LEE, Phillip, P.; Beyer Weaver & Thomas, LLP, P.O. Box 70250, Oakland, CA 94612-0250 (US).**

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(54) Title: **THERMOPHORETIC TECHNIQUES FOR PROTECTING RETICLES FROM CONTAMINANTS**



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(57) Abstract: Thermophoresis within lithography systems for protecting reticles from contaminants (e.g., floating particles). Generally, thermophoretic protection is implemented by maintaining the reticle at a higher temperature than its surrounding environment. Thermophoretic protection can be maintained throughout a reticle's use in a lithography system. For example, a reticle can be thermophoretically protected while in storage, through various stages of transportation via a reticle handler (also referred to as an end-effector), to its period of use while attached to a reticle chuck.



SI, SK, TR), OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ,
GW, ML, MR, NE, SN, TD, TG).

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